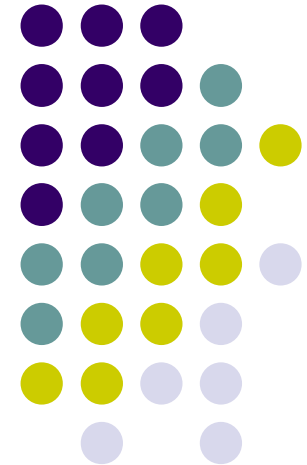


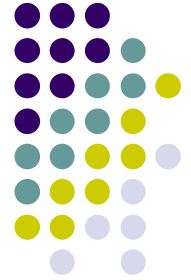
# An Efficient Algorithm for 3-D Reluctance Extraction Considering High Frequency Effect

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# Outline

- Background
- Partial reluctance extraction considering high frequency effect
- Efficient extraction of frequency-dependent reluctance
- Numerical results
- Conclusions

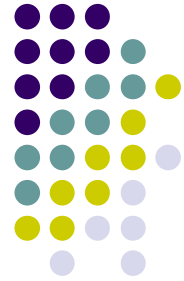


# Background

- Ultra deep sub-micron (even nano) technology is used
- Operating frequency reaches multiple giga-hertz
- Other factors:
  - Reduction of resistance by copper
  - Reduction of capacitance by low- $\kappa$  dielectric
  - High integrated density
  - Growing complexity of interconnect design

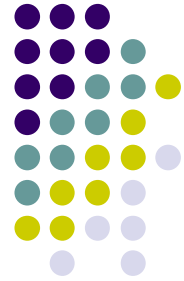


Efficient modeling of on-chip inductance effect becomes indispensable



# Background

- Main difficulty of on-chip inductance modeling
  - the unknown circuit return path before extraction and simulation
- PEEC (partial element equivalent circuit) model
  - Introducing the concept of partial inductance whose return path is at infinity
  - Coupling of partial inductance is among all the conductors, the resulted matrix is extremely dense
  - Simply truncating small terms leads system to unstable



# Background

- Partial reluctance (K element)
  - Attracts people's attention because of its good locality similar to capacitance
  - Ignoring small elements in matrix doesn't affect stability
  - Simulation based on it is more accurate and efficient
- Conventional partial reluctance extraction
  - Most works doesn't consider high frequency effect
  - High calculation complexity prohibits efficiency
  - Can't handle 3D complex structure well



# Background

- Direct extraction method
  - In [MTT-S04], YuDu presented a new method to capture partial reluctance
  - Extracts partial reluctance directly according to its physical meaning
  - Advantage: save calculation consumption
  - Unfortunately, still doesn't consider high frequency effect, not accurate enough

# Background

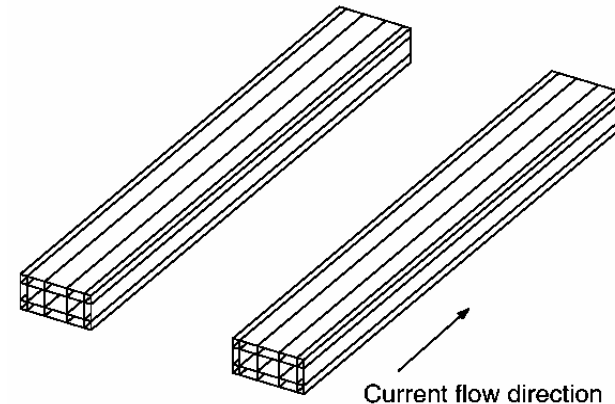


- Our contribution
  - Based on direct extraction method, meanwhile take high frequency effect into account
  - Applying efficient window selection strategy
  - Using other accelerating techniques
  - Achieve high accuracy and efficiency at the same time

# K extraction considering high frequency effect



- Capturing high frequency effect
  - Magneto quasi static (MQS) assumption
  - Current in a conductor isn't evenly distributed according to skin effect
  - Meshing non-uniformly



two parallel conductors meshed into  $5 \times 3$  filaments non-uniformly

- Frequency-dependent reluctance extraction
  - To use the locality property of partial reluctance, apply some window selection strategy
  - In each window,



# K extraction considering high frequency effect



- Formulate  $Z_m(\omega) = R_m(\omega) + j\omega L_m(\omega)$
- Set conductors to be aggressor one by one and calculate the admittance matrix  $Y_n$ , where m and n are number of filaments and conductors in the window respectively
- Inverse Y to get Z; calculate L; inverse L again to get K

$$Z_n(\omega) = Y_n^{-1}(\omega) \quad \longrightarrow \quad L_n(\omega) = \text{Im}\{Z_n(\omega)\} / \omega$$

Twice matrix inversion  $\longrightarrow$   $K_n(\omega) = L_n^{-1}(\omega)$

# K extraction considering high frequency effect



- Merge the local partial reluctance matrix with the global one
- The calculation complexity in each window is  $O(m^3)$  plus two matrix inversions of dimension  $n$
- Window selection strategy
  - Key issue to assure the accuracy of the extraction
  - Larger window size will bring higher accuracy as well as longer running time

For more detail, please refer to :

C. Luk 's paper on ASPDAC, pp. 793-798, Jan 2004

# K extraction considering high frequency effect



- Our method considers both shield effect and distance among conductors to determine a coupling level
- All conductors whose coupling level are less than a pre-specified 'max coupling level' form the current window
- One advantage: can handle general 3D structure well
- For general 3-D structures, perform projections of all the conductors in XOY, ZOX, and YOZ planes, respectively

# Efficient extraction of frequency dependent reluctance



- With the sinusoidal-steady assumption, we have

$$(R + j\omega L)I = V \xrightarrow{\text{filaments meshing}} (\hat{R} + j\omega \hat{L})\hat{I} = \hat{V} \quad (*)$$

where  $R$ ,  $L$  are the resistance matrix and the partial inductance matrix of the system

- According to the definition of  $K$  matrix,

$$j\omega I = K(V - RI)$$

which means the  $i$  th column of  $K$  matrix is numerically equal to the current distribution on the conductors if we set the  $i$  th entry (corresponding to the aggressor) of  $V - RI$  to  $j\omega$ , others to 0

# Efficient extraction of frequency dependent reluctance



- Physical meaning of partial reluctance
  - According to Faraday's law,  $\mathbf{E} = -j\omega\mathbf{A} - \nabla\Phi$   
where  $\mathbf{A}$  is the magnetic vector potential,  $\mathbf{E}$  is the electric field,  $\Phi$  is the scalar potential
  - Integrating both side, we have

$$V_{ab} = -(\Phi_b - \Phi_a) = j\omega \int_b^a \mathbf{A} d\mathbf{l} + \mathbf{E} \mathbf{l}_{ab}$$

- As  $\mathbf{E}$  contributes only to the resistance potential drop, so

$$V_{ab} - \mathbf{R}\mathbf{I} = j\omega \int_b^a \mathbf{A} d\mathbf{l}$$

which means the  $i$ th column of  $\mathbf{K}$  matrix is the current distribution on conductors if we set the  $i$ th entry of the vector potential drop to 1 and others to 0

# Efficient extraction of frequency dependent reluctance



- Relation between filament and conductor,

$$\hat{V} = M^t V \quad \text{and} \quad I = M \hat{I}$$

$$M_{ij} = \begin{cases} 1 & \text{when filament } j \text{ is in conductor } i \\ 0 & \text{otherwise} \end{cases}$$

We use the mesh incidence matrix  $M$  to describe the relation

- Rewrite Eq.(\*) (real and imaginary part respectively),

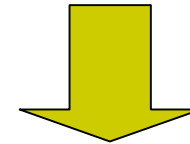
$$\begin{cases} \hat{R} \hat{I}_{re} - \omega \hat{L} \hat{I}_{im} = \hat{V}_{re} = M^t V_{re} \\ \omega \hat{L} \hat{I}_{re} + \hat{R} \hat{I}_{im} = \hat{V}_{im} = \omega M^t \int A dl \end{cases}$$

from the physical meaning, set the  $i$ th item to 1, the resulted current distribution is numerically equal to partial reluctance

# Efficient extraction of frequency dependent reluctance



- Under the special vector potential drop setting, the current distribution numerically equals to one column of  $K$  matrix



- We know  $K$  matrix is real   $I_{im} = 0$

- Add this equation to the previous system, we can finally get the whole system
- Condensing the system
  - Since  $I$  is real, we don't need to know the imaginary part
  - Delete the corresponding variables from the original system

# Efficient extraction of frequency dependent reluctance



original system

$$\begin{bmatrix} \hat{R} & -\omega\hat{L} & -M^t \\ \omega\hat{L} & \hat{R} & 0 \\ 0 & M & 0 \end{bmatrix} \begin{bmatrix} \hat{I}_{re} \\ \hat{I}_{im} \\ V_{re} \end{bmatrix} = \begin{bmatrix} 0 \\ \omega M^t \int Adl \\ 0 \end{bmatrix}$$

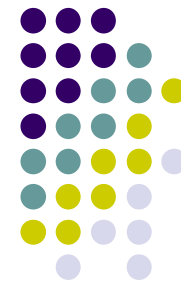
delete  $\hat{I}_{im}$  from the original system

condensed system

$$\begin{bmatrix} I + (\omega\hat{R}^{-1}\hat{L})^2 & -\hat{R}^{-1}M^t \\ M\hat{R}^{-1}\hat{L} & 0 \end{bmatrix} \begin{bmatrix} \hat{I}_{re} \\ V_{re} \end{bmatrix} = \begin{bmatrix} \omega^2\hat{R}^{-1}\hat{L}\hat{R}^{-1}M^t \int Adl \\ M\hat{R}^{-1}M^t \int Adl \end{bmatrix}$$

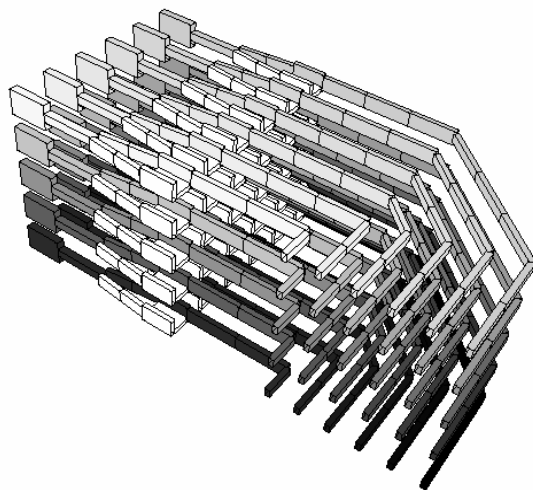
- The dimension of coefficient matrix is decreased from  $2m+n$  to  $m+n$
- Since  $m \gg n$ , condensing can cut solving time a lot
- With little extra consumption



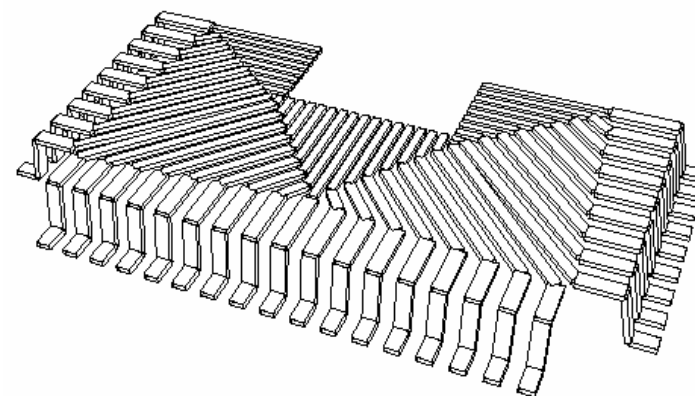


# Numerical results

- Three typical structures (two from real industry)
  - Example 1 A randomly generated structure, containing 300 parallel conductors with unequal length



Example 2 A 30 pins real industry package structure contains 260 conductors  
Numbers partitioned level:  $3 \times 3$



Example 3 A 35 pins real industry package structure contains 175 conductors  
Numbers partitioned level:  $3 \times 5$



# Numerical results

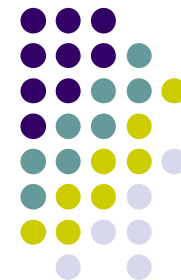
- All examples are extracted under operating frequency of 10GHz
- We compare our result with FastHenry
- First extract partial reluctance; then reverse it to get the partial inductance matrix
- Use loop error distribution to measure the accuracy

TABLE I Computational Time for the Examples (Unit in Second)

	FastHenry	Our algorithm	Speed-up ratio
example 1	855.2	9.12	94
example 2	5650.2	9.83	575
example 3	5796.3	122.51	47

The results of FastHenry are based on default preferences.

CPU time of all experiments are recorded on a Sun Ultra V880 server (frequency 750MHz).



# Numerical results

TABLE II Error Distribution of Loop Inductance (Compared with FastHenry)

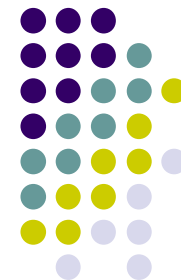
Error of loop inductance(%)	<3%	3-6%	6-9%	9-12%	12-15%	>15%
example 1	95.5%	4.2%	0.3%	0.0%	0	0
example 2	46.4%	26.4%	12.3%	6.8%	2.5%	5.1%
example 3	72.7%	20.7%	5.7%	0.8%	0.1%	0.0%

- The result indicates the accuracy of example 2 is not as good as the others. Because the locality of partial reluctance in example 2 is not so good
- Partial reluctance has ‘good locality’ relative to partial inductance. It doesn’t means the locality is very good in any structure



# Conclusions

- Conclusions
  - Less accuracy (due to without high frequency effect consideration), too much calculation consumption, are shortcomings of most conventional methods
  - An efficient algorithm based on direct partial reluctance extraction is proposed
  - Taking high frequency effect into account, the algorithm shows high accuracy and several 10X ~ 100X speedup over FastHenry
- Future work
  - Further improvement of equation solution
  - Apply this algorithm in partial reluctance based circuit simulation



# Thank you !

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